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October 27, 2014

Brian Toohey

President and CEO, Semiconductor Industry Association

Dear Brian,

The WSC Intellectual Property Committee (IPC) would like to directly bring to your attention one of its recent significant accomplishments.

You may recall that the IPC has been working on a Patent Quality Initiative for some time, as it has been identified as one of the most effective ways to improve all patent systems. There are many positive effects of improving patent quality, including eliminating the wasteful use of our fiscal and employee resources to defend the assertion of low quality patents by patent holders, including NPE's and PAE's.

One patent quality project in particular the IPC undertook was to create a plan for the IPC member countries and regions to harmonize their Patent Quality Metrics. The metrics prescribe a set of checks and balances throughout the patent application examination process, as well as required information to use to corroborate the overall quality. This will ensure a high quality examination of all patent applications using common practices, and provide assurance to patent applicants that their granted patents will ultimately have the same level of quality in all of the participating countries and regions. It will also allow for a meaningful comparison of public reports on patent quality from each participating patent office and the monitoring of progress of quality improvements. Most importantly, this harmonized approach will provide more legal certainty and predictability to both patent holders and patent users.

In order to implement the recommendations from this project, the IPC communicated directly with WIPO and the IP5 (Patent Offices of US, EPC, Japan, Korea and China) to encourage adoption of our recommendations. As a result of this effort, we are happy to report that both the WIPO MIA (Meeting of International Authorities) and the IP5 have created a committee to work on harmonized patent quality. Their first meetings on the topic were conducted the week of October 13<sup>th</sup>, 2014 in Beijing.



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What is most noteworthy regarding this effort is the feedback that we received from WIPO. WIPO indicated that IPC work in driving Patent Quality metrics at WIPO and the IP5 on the topic, “broke the ice”, such that the IP5 subcommittee on quality is now working on this, as is the MIA (meeting of international authorities) in WIPO.

The IPC wishes to thank you for your support on this important and productive endeavor.

A handwritten signature in blue ink that reads "Belinda HU". The signature is written in a cursive, flowing style.

Belinda HU

Chair of the WSC IP Committee

Cc: Devi Bengfort Keller, Deputy Director, Global Policy, Semiconductor Industry Association